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APPLICATION NO.	FILING	DATE	FIRST NAMED INVENTOR	ATTORNEY DOX:KET NO.	CONFIRMATION NO.	
10/768,038	0/768,038 02/02/2004		Eijchi Okutsu	FS-F03226-01	7584	
37398	7590	05/18/2005		EXAM	EXAMINER	
	RPORATIO		CHEA, THORL			
2111 JEFFERSON DAVIS HIGHWAY #412. NORTH			ART UNIT	PAPER NUMBER		
ARLINGTO	ARLINGTON, VA 22202			1752		
				DATE MAILED: 05/18/2005	5	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
Office Action Summary		10/768,038	OKUTSU ET AL.				
Office	action Summary	Examiner	Art Unit				
The MAIL IA	IO DATE of this assessmin time as	Thori Chea	1752				
Period for Reply	IG DATE of this communication app	ears on the cover sheet with the c	orrespondence address				
THE MAILING DA - Extensions of time may after SIX (6) MONTHS - If the period for reply sp - If NO period for reply is - Failure to reply within the Any reply received by the	TATUTORY PERIOD FOR REPLY TE OF THIS COMMUNICATION. To be available under the provisions of 37 CFR 1.13 from the mailing date of this communication. Decified above is less than thirty (30) days, a reply specified above, the maximum statutory period whe set or extended period for reply will, by statute, the Office later than three months after the mailing sustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status							
1) Responsive	to communication(s) filed on 02 Fe	ebruary 2004.					
2a) This action i		action is non-final.					
3) Since this ap	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in ac	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims	S						
4)⊠ Claim(s) <u>1-2</u>	0 is/are pending in the application.	•					
4a) Of the ab	4a) Of the above claim(s) is/are withdrawn from consideration.						
5)☐ Claim(s)	Claim(s) is/are allowed.						
	Claim(s) <u>1-20</u> is/are rejected.						
	Claim(s) is/are objected to.						
8) Claim(s)	Claim(s) are subject to restriction and/or election requirement.						
Application Papers							
9) The specifica	ation is objected to by the Examiner	r.					
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.							
Applicant may	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11)∐ The oath or d	leclaration is objected to by the Exa	aminer. Note the attached Office	Action or form PTO-152.				
Priority under 35 U.S	.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). 							
* See the attached detailed Office action for a list of the certified copies not received.							
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Address to the second of the s							
Attachment(s) 1) Notice of References	Cited (PTO 802)	∆ □	(DTO 110)				
2) 🔲 Notice of Draftspersor	n's Patent Drawing Review (PTO-948)	4)					
3) Information Disclosure Paper No(s)/Mail Date	Statement(s) (PTO-1449 or PTO/SB/08)	5) ☐ Notice of Informal Pa 6) ☐ Other:	atent Application (PTO-152)				

DETAILED ACTION

Specification

1. Claims 1-2 are objected to because of the following informalities: the term "smaller" should be changed to "less" or "shorter" since this term modify the "distance". See claim 1, line 11 and claim 2, line 4. Appropriate correction is required.

Claim Rejections - 35 USC § 112

- 2. The following is a quotation of the second paragraph of 35 U.S.C. 112:
 - The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 3. Claims 1-20 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. The claiming of an "alkyl group having an unsaturated bond" is unclear in view of conventionally known as an "alkyl group". The alkyl group known in the art is the group " C_nH_{2n+1} , and there is no unsaturated bond associated therein. Accordingly, the claiming of "alkyl group having an unsaturated bond" is indefinite.

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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5. Claims 11-20 are rejected under 35 U.S.C. 103(a) as being unpatentable over the combination of Morita et al (US 2003/0215756), Fukui et al (US Patent No. 5,041,369) and Kudo (US 2004/0005521).

Morita et al disclose a photothermographic material containing a composition of two bisphenol compounds, the bisphenol of formula A-1 and the bisphenol of formula A-2. The bisphenol A-2 is within the scope of formula (R1) of the claimed invention. See exemplified samples on pages 18-23, compound I-18 to I-65. The compound of formula A-1 differs from the compound of formula (R2), X in the formula (A-1) is a chalcogen or CHR, wherein R is a hydrogen or an alkyl group. The material is process within a period of 1 sec. to 2 mn at a temperature of 80 °C to 200 °C. See page 42, [0352], [0353]; see also the apparatus of Fig 1 and the description thereof on page 42, [0350] having exposure portion (120) and developing section 130; the laser scanning exposure in column 41, [0338] to [0348]; and the silver coverage from 0.3 to 1.5 g/m² on page 30, [0329]. Fukui et al disclose the bisphenol within the scope of formula (R2) in column 7. formula (III) wherein Z represent a divalent group such as alkyldiene group, an aralkyldiene group, or a sulfur; similarly Kudo discloses the claimed bisphenol on page 16 such as compound A-17 and A-20. Morita et al differs from the claimed invention in its failure to discloses the alkenyl group and an alkyl group having unsaturated bond claimed in the present claimed invention. However, the group as claimed have been known to use in association with a divalent group of a bisphenol compound such as taught in Fukui et al and Kudo. It would have been obvious to the worker of ordinary skill in the art at the time the invention was made to use a divalent group such as alkyldiene group which is a known equivalent to an alkyl group or a chalcogen in

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combination with a known heating process for forming an image with time of 1 sec. to 2 mn such as suggested Morita et al with a reasonable expectation of achieving a material with high photographic density, improved image tone and image stability.

6. Claims 1-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over the combination of Morita et al (US 2003/0215756), Fukui et al (US Patent No. 5,041,369) and Kudo (US 2004/0005521).

Morita et al disclose a photothermographic material containing a composition of two bisphenol compounds, the bisphenol of formula A-1 and the bisphenol of formula A-2. The bisphenol A-2 is within the scope of formula (R1) of the claimed invention. See exemplified samples on pages 18-23, compound I-18 to I-65. The compound of formula A-1 differs from the compound of formula (R2), X in the formula (A-1) is a chalcogen or CHR, wherein R is a hydrogen or an alkyl group. The material is process within a period of 1 sec. to 2 mn at a temperature of 80 °C to 200 °C. See page 42, [0352], [0353]; see also the apparatus of Fig 1 and the description thereof on page 42, [0350] having exposure portion (120) and developing section 130; the laser scanning exposure in column 41, [0338] to [0348], and the silver coverage from 0.3 to 1.5 g/m² on page 30, [0329]. Fukui et al disclose the bisphenol within the scope of formula (R2) in column 7, formula (III) wherein Z represent a divalent group such as alkyldiene group, an aralkyldiene group, or a sulfur; similarly Kudo discloses the claimed bisphenol on page 16 such as compound A-17 and A-20. Morita et al differs from the claimed invention in its failure to discloses the alkenyl group and an alkyl group having unsaturated bond, and distance between the scanning line of the laser irradiating mean and inserting portion of the thermal developing unit of equal to or smaller than 50 cm present in the claimed

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invention. However, the group as claimed have been known to use in association with a divalent group of a bisphenol compound such as taught in Fukui et al and Kudo, and the distance of the laser exposure mean and the heating unit may vary accordingly to the size of the apparatus. It would have been obvious to the worker of ordinary skill in the art at the time the invention was made to use a divalent group such as alkyldiene group which is a known equivalent to an alkyl group or a chalcogen in combination with the use of the apparatus suggested Morita et al with a reasonable expectation of achieving a material with high photographic density, improved image tone and image stability. The worker of ordinary skill in the art would prefer to use the exposure unit close to the heat developing unit in order to reduce the processing time.

7. Claims 1-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over the Morita et al (US 2003/0215756) in view of Fukui et al (US Patent No. 5,041,369) or Kudo (US 2004/0005521) further in view of Oyamada et al (US 2004/0038156) or Yamane (US 6,800,427).

Morita et al disclose a photothermographic material containing a composition of two bisphenol compounds, the bisphenol of formula A-1 and the bisphenol of formula A-2. The bisphenol A-2 is within the scope of formula (R1) of the claimed invention. See exemplified samples on pages 18-23, compound I-18 to I-65. The compound of formula A-1 differs from the compound of formula (R2), X in the formula (A-1) is a chalcogen or CHR, wherein R is a hydrogen or an alkyl group. The material is process within a period of 1 sec. to 2 mn at a temperature of 80 °C to 200 °C. See page 42, [0352], [0353]; see also the apparatus of Fig 1 and the description thereof on page 42, [0350] having exposure portion (120) and developing section 130; the laser scanning exposure in

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column 41, [0338] to [0348]; and the silver coverage from 0.3 to 1.5 g/m² on page 30, [0329]. Fukui et al disclose the bisphenol within the scope of formula (R2) in column 7. formula (III) wherein Z represent a divalent group such as alkyldiene group, an aralkyldiene group, or a sulfur; similarly Kudo discloses the claimed bisphenol on page 16 such as compound A-17 and A-20. Yamane and Oyamada et al each discloses a heat development apparatus wherein the exposure unit close to the heat development unit. Morita et al differs from the claimed invention in its failure to discloses the alkenyl group and an alkyl group having unsaturated bond, and distance between the scanning line of the laser irradiating mean and inserting portion of the thermal developing unit of equal to or smaller than 50 cm present in the claimed invention. However, the group as claimed have been known to use in association with a divalent group of a bisphenol compound such as taught in Fukui et al and Kudo, and the apparatus wherein the exposure unit close to the heat development unit are in short distance from one to to another have been known in Yamane and Oyamada. It would have been obvious to the worker of ordinary skill in the art at the time the invention was made to use a divalent group such as alkyldiene group which is a known equivalent to an alkyl group or a chalcogen in combination with the use of the apparatus taught in Yamada or Oyamada et al with a reasonable expectation of achieving a material with high photographic density, improved image tone and image stability.

Conclusion

8. The lengthy specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

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9. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Thorl Chea whose telephone number is (571) 272-1328.

The examiner can normally be reached on 9 AM-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Cynthia H. Kelly can be reached on (571)272-1526. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

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have questions on access to the Private PAIR system, contact the Electronic Business

Center (EBC) at 866-217-9197 (toll-free).

Thorl Chea

Primary Examiner

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Tch (M)
May 13, 2005